Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S38	4382	(438/427,692,697).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/24 17:28
S39	99358	"STI" insolation near3 trench "shallow trench isolation" "LOCOS" "FOX" local near3 oxidation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/24 17:28
S40	67231	("cmp" chemical adj mechanical adj polishing)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/24 17:28
S41	1310	nitride with polish\$3 near stop\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON.	2006/02/24 17:29
S42	10153	nitride with (polish\$3 near stop\$3 etch\$3 near stop\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/24 17:30
S43	48	S39 with S40 with S42	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/02/24 17:33
S44	1270014	(dop\$4 impurit\$3 (ion near3 implant\$6) diffus\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 12:04
S45	71	S41 with S44	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2006/02/24 17:32
S46	0	S39 with S40 with S45	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/24 17:33

S47	23	S39 with S40 and S45	US-PGPUB;	OR	ON	2006/02/24 17:33
			USPAT; EPO; JPO; DERWENT; IBM_TDB			
S48	29	("5250829").URPN.	USPAT	OR	OFF	2006/02/26 21:10
S49	9	("4688063" "4794434" "4801988" "4829017" "4873560" "4912054" "4918502" "4944682" "5079613").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/27 07:33
S50	1	10/791759	US-PGPUB; USPAT; USOCR	OR	OFF	2006/03/21 11:21
S51	29	("5250829").URPN.	USPAT	OR	OFF	2006/02/27 07:42
S52	29	S51 and (dop\$4 impurit\$3 (ion near3 implant\$6) diffus\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/27 07:42
S53	823933	(dop\$4 impurit\$3 (ion near3 implant\$6) diffus\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/27 07:43
S54	8888	(dop\$4 impurit\$3 (ion near3 implant\$6) diffus\$4) near3 nitride	US-PGPUB; USPAT; USOCR	OR .	OFF	2006/02/27 07:43
S55	15742	(dop\$4 impurit\$3 (ion near3 implant\$6) diffus\$4) near5 nitride	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/27 07:43
S56	16536	(dop\$4 impurit\$3 (ion near3 implant\$6) diffus\$4) near5 nitride	US-PGPUB; USPAT; USOCR	OR	ON .	2006/02/27 07:45
S57	7	S51 and S56	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 07:45
S58	99363	"STI" insolation near3 trench "shallow trench isolation" "LOCOS" "FOX" local near3 oxidation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 07:45
S59	6	S57 and S58	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:01
S60	642571	planrized planar planarization polish\$3 planarity	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 12:05
S61	14218	nitrfy nitrifying nitrification nitried nitridation nitriding nitrogen-dopant	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:06

S62	14273	nitrify nitrifying nitrification nitried	US-PGPUB;	OR	ON	2006/02/27 08:07
		nitridation nitriding nitrogen-dopant	USPAT; USOCR			
S63	203	S60 with S62	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:07
S64	0	S63 with "17"	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:08
S65	0	S63 with S56	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:08
S66	1	S63 same S56	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:09
S67	47	S63 and S56	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:14
S68	1310	nitride with polish\$3 near stop\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2006/02/27 08:17
S69	1068	S68 and (openning trench groove cavity recess\$3)	US-PGPUB; USPAT; USOCR	OR .	ON	2006/02/27 08:18
S70	2060035	(openning trench groove cavity recess\$3)	US-PGPUB; USPAT; USOCR	OR:	ON	2006/02/27 16:14
S71	358	S70 with S62	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:20
S72	29	S71 with S60	US-PGPUB; USPAT; USOCR	OR	ON .	2006/02/27 08:20
S73	. 0	S72 with S56	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:20
S74	190	S62 with S56	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 08:20
S75	5	S70 with S74	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 11:34

					r	·····
S76	1431614	(dop\$4 impurit\$3 (ion near3 implant\$6) implant\$6 diffus\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 12:04
S77	3217	nitride near3 (planrized planar planarization polish\$3 planarity)	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:16
S78	. 73	S76 same S77 same (source near drain 'source/drain' 'source and darin')	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 12:07
S79	84	S76 same S77 same (source near drain 'source/drain' 'source and drain')	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 15:58
S80	14273	nitrify nitrifying nitrification nitried nitridation nitriding nitrogen-dopant	US-PGPUB; USPAT; USOCR	OR	ON	2006/03/21 15:57
S81	194	S76 same S80 same (source near drain 'source/drain' 'source and drain')	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 12:09
S82	50	("5376578").URPN.	USPAT .	OR	OFF	2006/02/27 14:57
S83	194	S81 not S79	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 15:58
S84	99363	"STI" insolation near3 trench "shallow trench isolation" "LOCOS" "FOX" local near3 oxidation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 15:58
S85	81	S83 and S84	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 15:59
S86	10153	nitride with (polish\$3 near stop\$3 etch\$3 near stop\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/27 16:13
S87	2060035	(openning trench groove cavity recess\$3)	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:14
S88.	350225	insulat\$3 near3 material	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:15
S89	41149	S88 near5 fil\$3	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:15

			T		-1	
S90	21955	S88 near5 fill\$3	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:15
S91	642571	(planrized planar planarization polish\$3 planarity)	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:17
S92 .	4149449	(CMP polish\$4 abra\$6 planariz\$6 grind\$4 lap\$4) remov\$4 etch\$4	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:18
S93	18343	S84 same S87	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:18
S94	1646	S84 same S87 same S88	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:18
S95	826	S84 same S87 same S88 same S90	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:19
S96	222	S84 same S87 same S88 same S90 same S91	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:19
S97	220	S84 same S87 same S88 same S90 same S91 same S92	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:44
S98	12	S84 same S87 same S88 same S90 same S91 same S92 same S86	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 16:20
S99	161	S97 and (nm nanometer nano adj meter angstrom ang ".ang.")	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 18:27
S10 0	7	"5702976".pn. "6436808".pn. "6140691".pn. "5943585".pn. "6087705".pn. "5811347".pn. "6344415".pn.	US-PGPUB; USPAT; USOCR	OR .	ON	2006/02/27 18:27
S10 1	5	S100 and (nm nanometer nano adj meter angstrom ang ".ang.")	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:54
S10 2	2	S96 not S97	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:53
S10 3	185318	(nitride silicon adj nitride)	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:53
S10 4	9614	S84 same S103	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:56

S10 5	3273	S104 same (nm nanometer nano adj meter angstrom ang ".ang.")	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:56
S10 6	4272031	S91 S92	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:55
S10 7	2372	S105 same S106	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:55
S10 8	5047	S84 with S103	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 19:56
S10 9	397	S108 with (nm nanometer nano adj meter angstrom ang ".ang.")	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/28 08:24
S11 0	163	S109 with S106	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 20:17
S11 1	234	S109 not S110	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/27 20:17
S11 2	603094	(nm nanometer nano adj meter angstrom ang ".ang.")	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/28 08:25
S11 3	38536	(resist hard) adj (mark mask\$4) etch\$4 adj stop	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/28 08:26
S11 4	4085	(257/118,244,328-333,466,513, 594).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 11:33
S11 5	3115	(438/242,268-274).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 11:41
S11 6	3322	(438/690,692,693,940,959).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2006/03/21 11:42
S11 7	2493	(257/E21.214,E21.237-E21.239). CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR ·	OFF	2006/03/21 11:43

				1	1	
S11 8	12494	S114 S115 S116 S117	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 15:55
S11 9	6434	S115 S116	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 12:54
S12 0	1693	438/424.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2006/03/21 12:55
S12 1	2367	(257/e21.54,e21.545,e21.564). CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 14:44
S12 2	4085	(257/118,244,328-333,466,513,594).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 15:55
S12 3	3115	(438/242,268-274).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 15:55
S12 4	3322	(438/690,692,693,940,959).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 15:55
S12 5	2493	(257/E21.214,E21.237-E21.239). CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR ··	OFF	2006/03/21 15:55
S12 6	12494	S122 S123 S124 S125	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 15:55
S12 7	12494	S126 S125	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/21 15:55

S12 8	255	S127 and (polish adj stop "polish stop" barier adj layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/21 15:56
S12 9	6	S128 and (nitrify nitrifying nitrification nitried nitridation nitried nitridation nitriding nitrogen-dopant)	US-PGPUB; USPAT; USOCR	OR	ON	2006/03/21 15:58
S13 2	1	nitride near polish\$3 and stop near layer and (STI shallow adj trench adj isolation) and etch\$3 and impurity.clm.	US-PGPUB	OR	ON	2006/03/21 18:14
S13 3	1	(nitride near polish\$3) near5 (stop near layer) and (STI shallow adj trench adj isolation) and etch\$3 and impurity.clm.	US-PGPUB	OR	ON	2006/03/21 17:21
S13 4	20	(nitride near polish\$3) near5 (stop near layer)	US-PGPUB	OR	ON	2006/03/21 18:20
S13 5	8432	(STI shallow adj trench adj isolation)	US-PGPUB	OR	ON	2006/03/21 18:21
S13 6	1	S134 same S135 same impurity	US-PGPUB	OR	ON	2006/03/21 18:23
S13 7	120	(nitride near polish\$3) near5 (stop near layer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/21 18:20
S13 8	223743	(STI shallow adj trench adj isolation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/21 18:21
S13 9	1	S137 same S138 same impurity	US-PGPUB	OR	ON	2006/03/21 18:23

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L11	1	nitride near polish\$3 and stop near layer and (STI shallow adj trench adj isolation) and etch\$3 and impurity.clm.	US-PGPUB	OR	ON	2006/03/21 18:14